US00D352911S

United States Patent [19]

Yamamoto et al.

[11] **Patent Number: Des. 352,911**

[45] **Date of Patent: ** Nov. 29, 1994**

[54] **PROCESSING MACHINE FOR ELECTRON BEAM LITHOGRAPHY SYSTEM**

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[73] Assignee: **Hitachi, Ltd.**, Tokyo, Japan

[**] Term: **14 Years**

[21] Appl. No.: **4,587**

[22] Filed: **Feb. 8, 1993**

[30] **Foreign Application Priority Data**

Nov. 27, 1992 [JP] Japan 34703/1992

[52] **U.S. Cl.** **D10/75**; D10/46

[58] **Field of Search** .... 250/492.2, 492.3, 492.22, 250/492.23, 396 R, 310, 306, 307; 219/121.25, 121.27; D10/75, 46; D18/50; D14/100, 102, 106

[56] **References Cited**

U.S. PATENT DOCUMENTS

D. 342,909	1/1994	Marchais	D10/75
D. 344,719	3/1994	Wang et al.	D14/102 X

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[57] **CLAIM**

The ornamental design for a processing machine for electron beam lithography system, as shown and described.

DESCRIPTION

FIG. 1 is a front, top and right side elevational perspective view of a processing machine showing our new design;

FIG. 2 is a front elevational view thereof;

FIG. 3 is a right elevational view thereof;

FIG. 4 is a left elevational view thereof;

FIG. 5 is a top plan elevational view thereof;

FIG. 6 is a bottom plan elevational view thereof;

FIG. 7 is a rear elevational view thereof; and,

FIG. 8 is a front, top and right side elevational perspective view thereof in condition that a drawer on which a keyboard and a mouse pad is disposed.

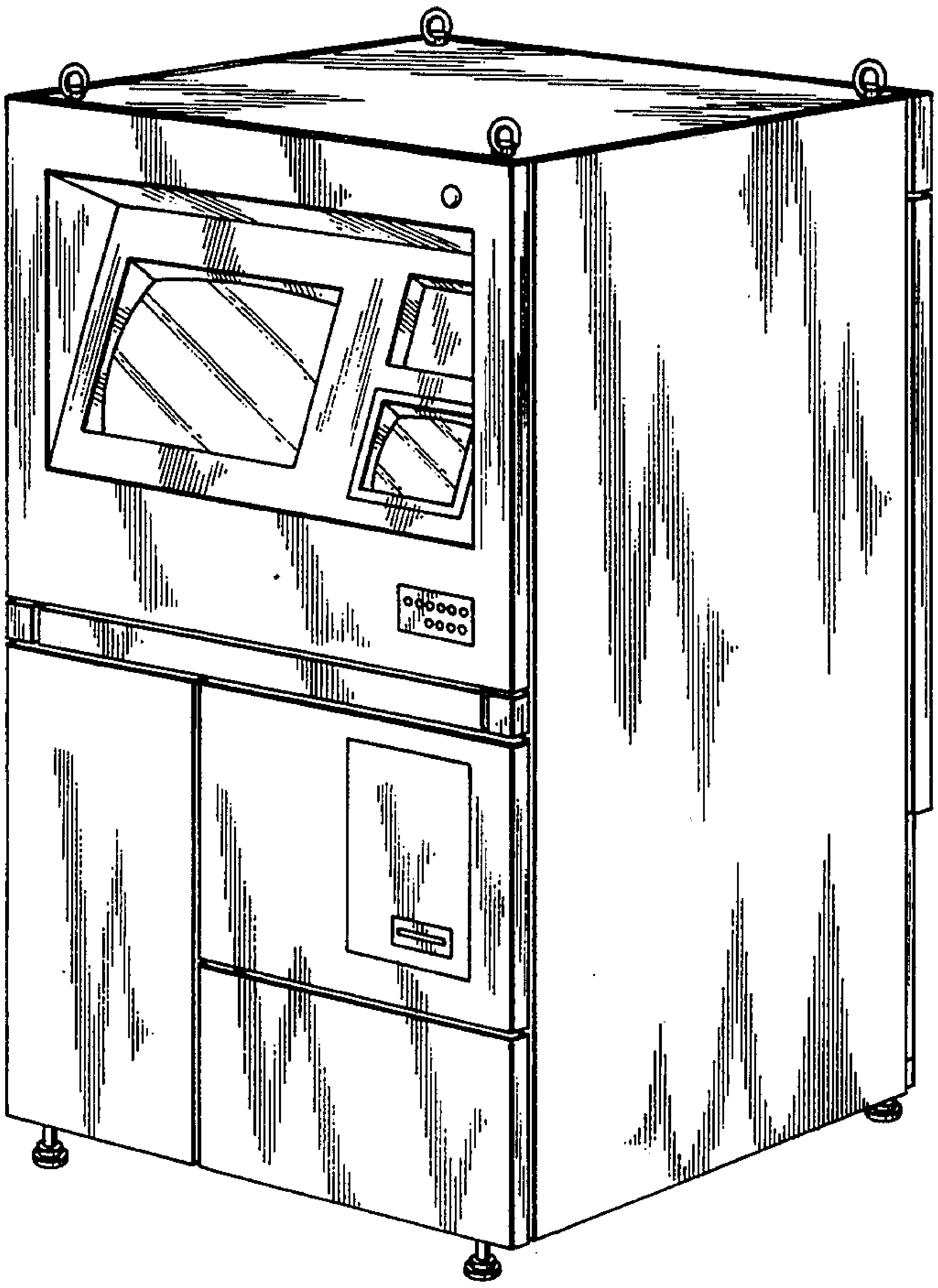

FIG. 1

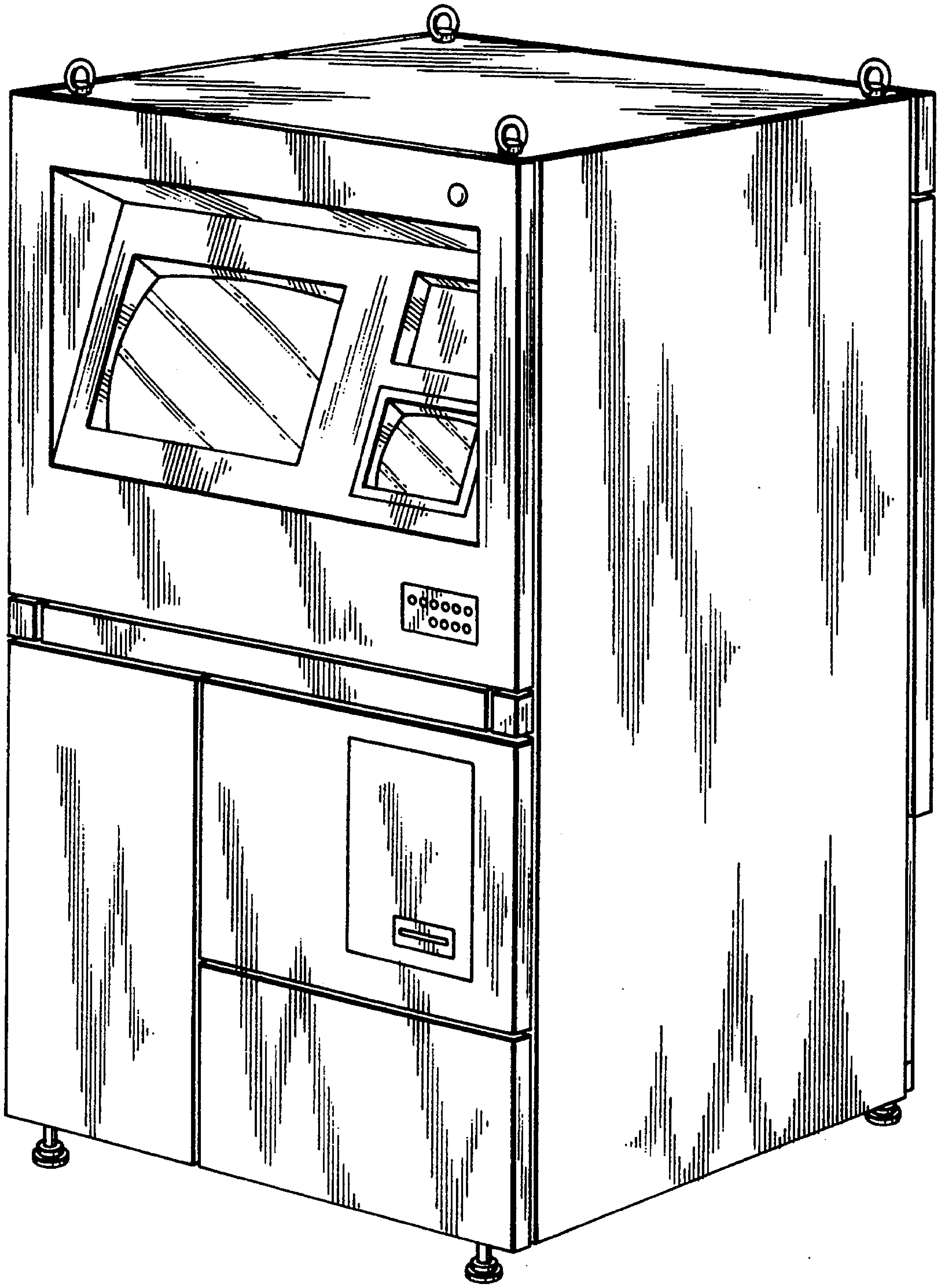

FIG. 2

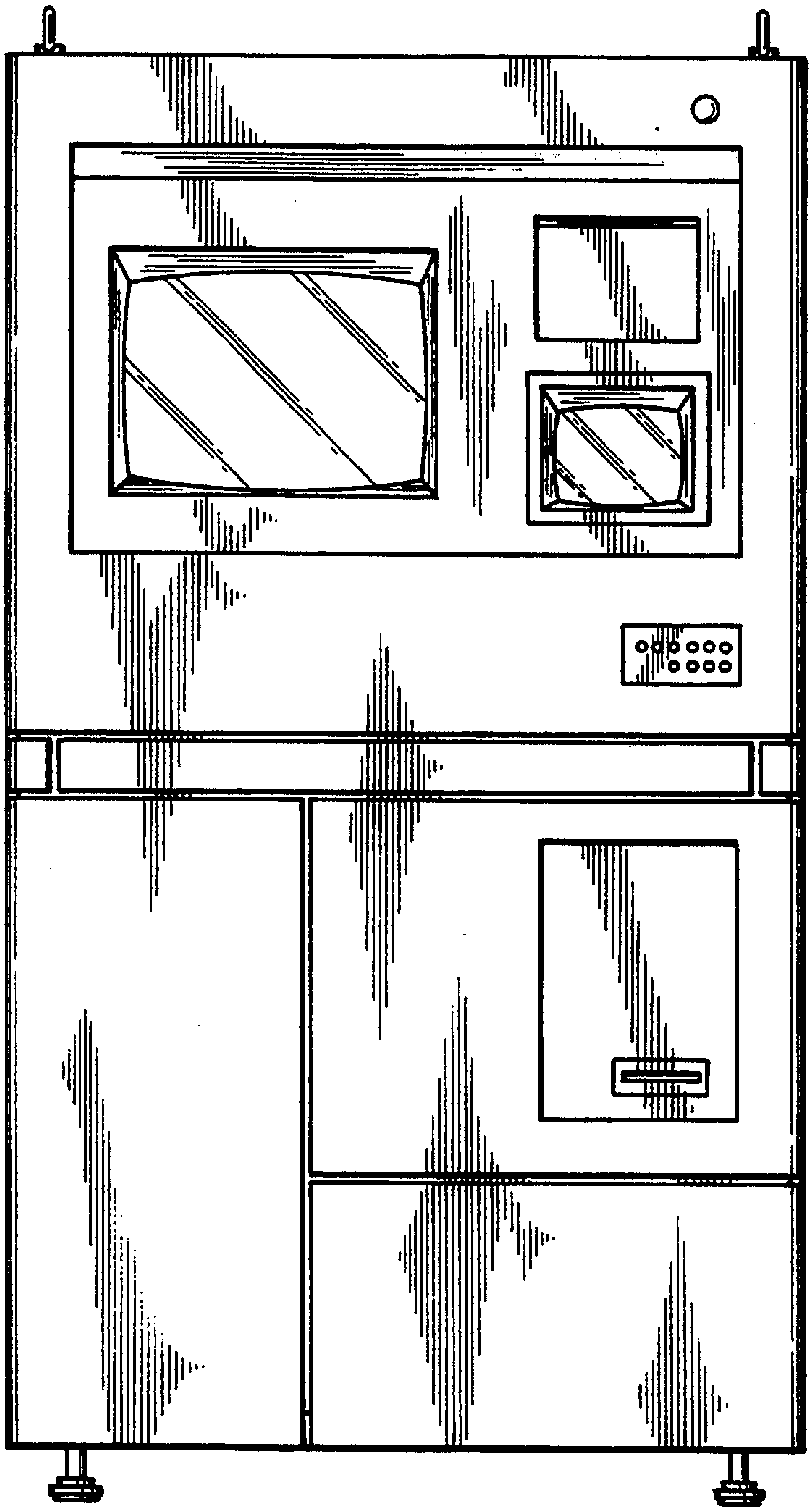

FIG. 3

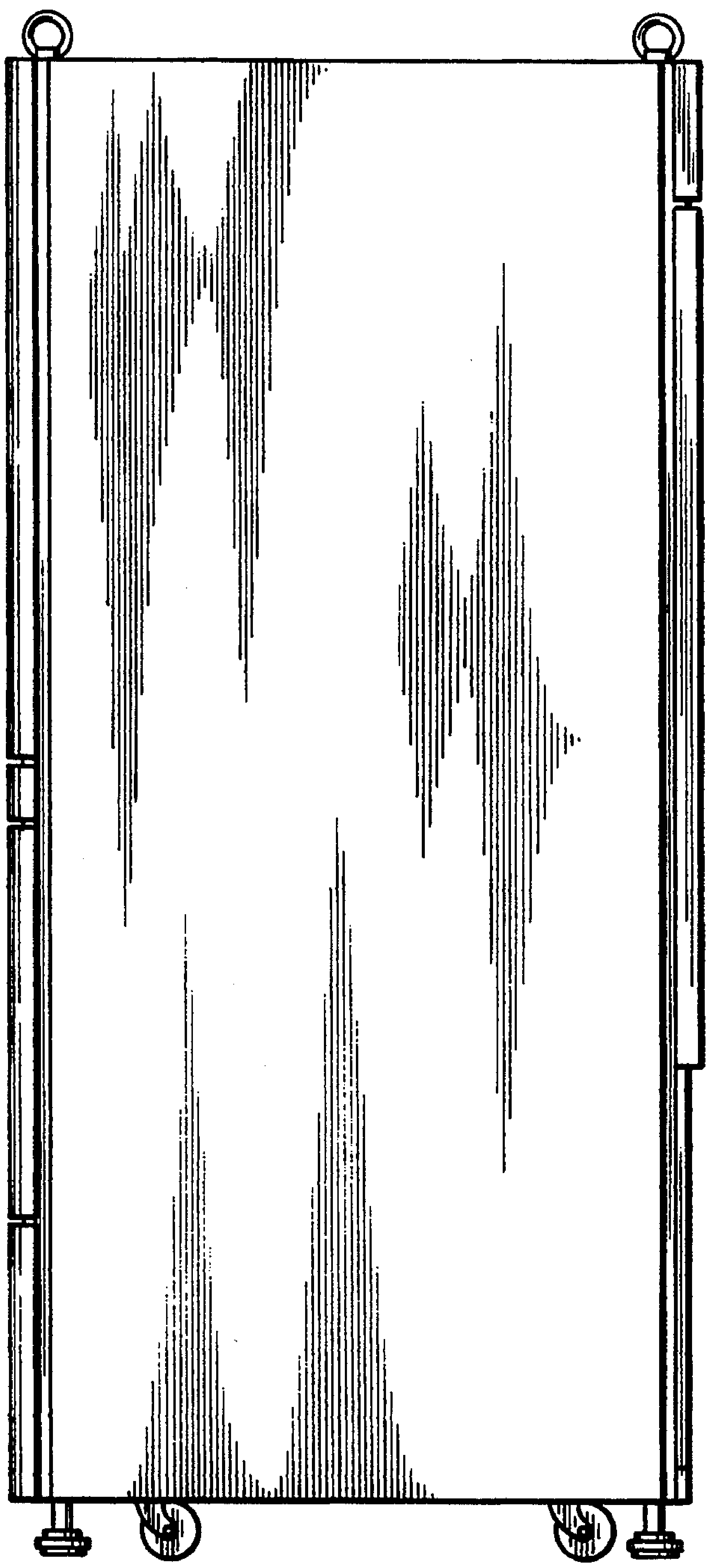

FIG. 4

FIG. 5

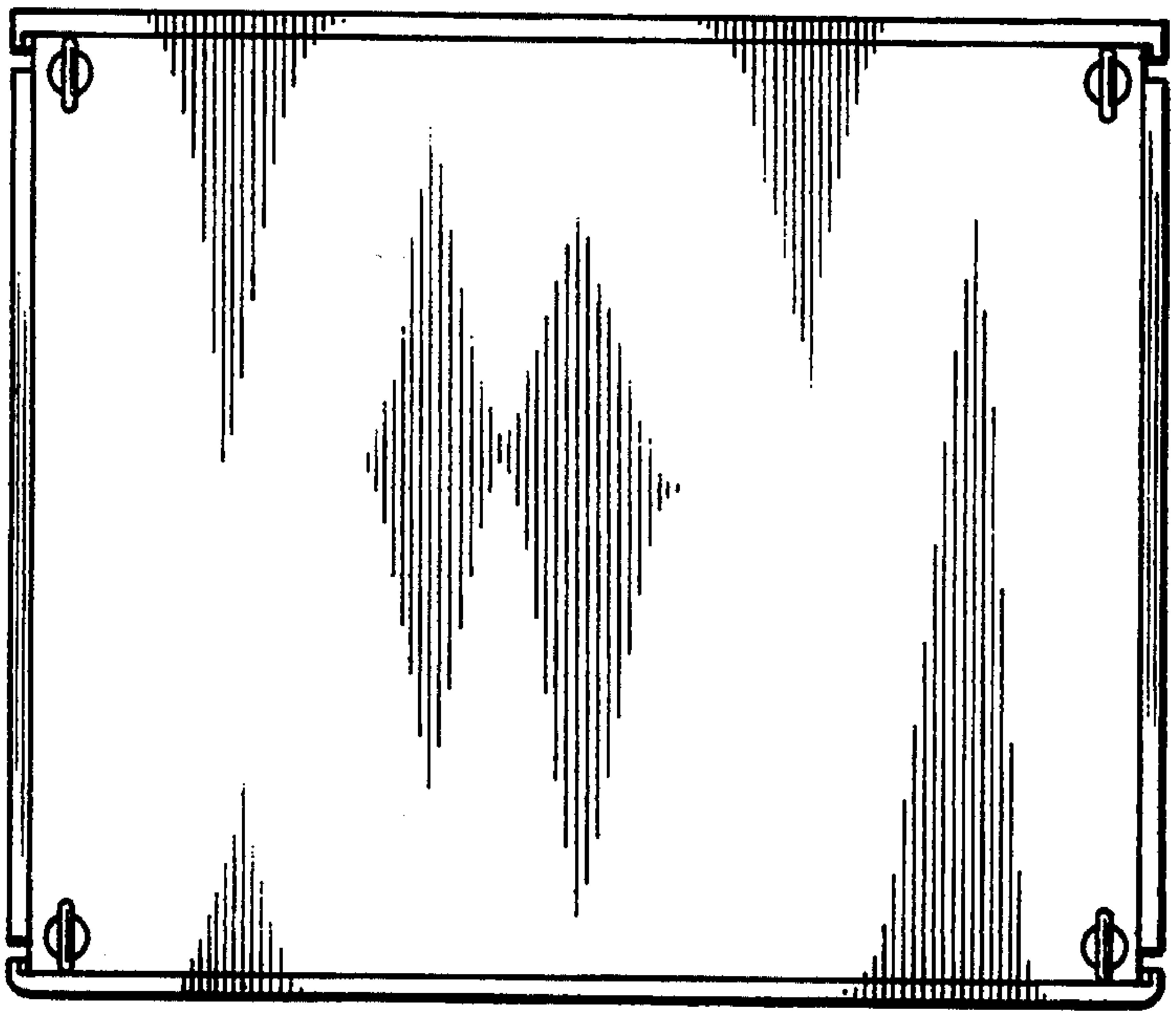

FIG. 6

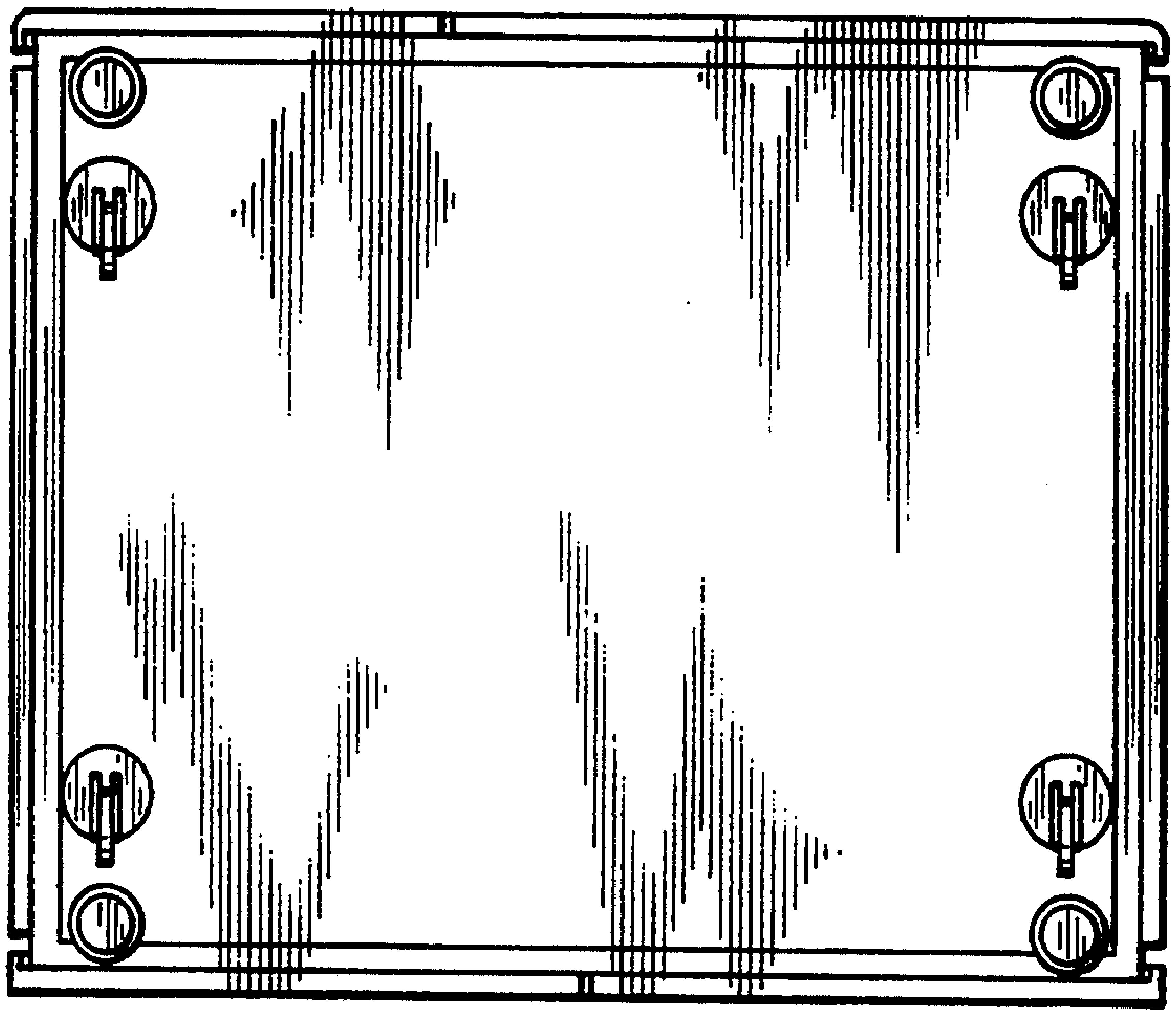

FIG. 7

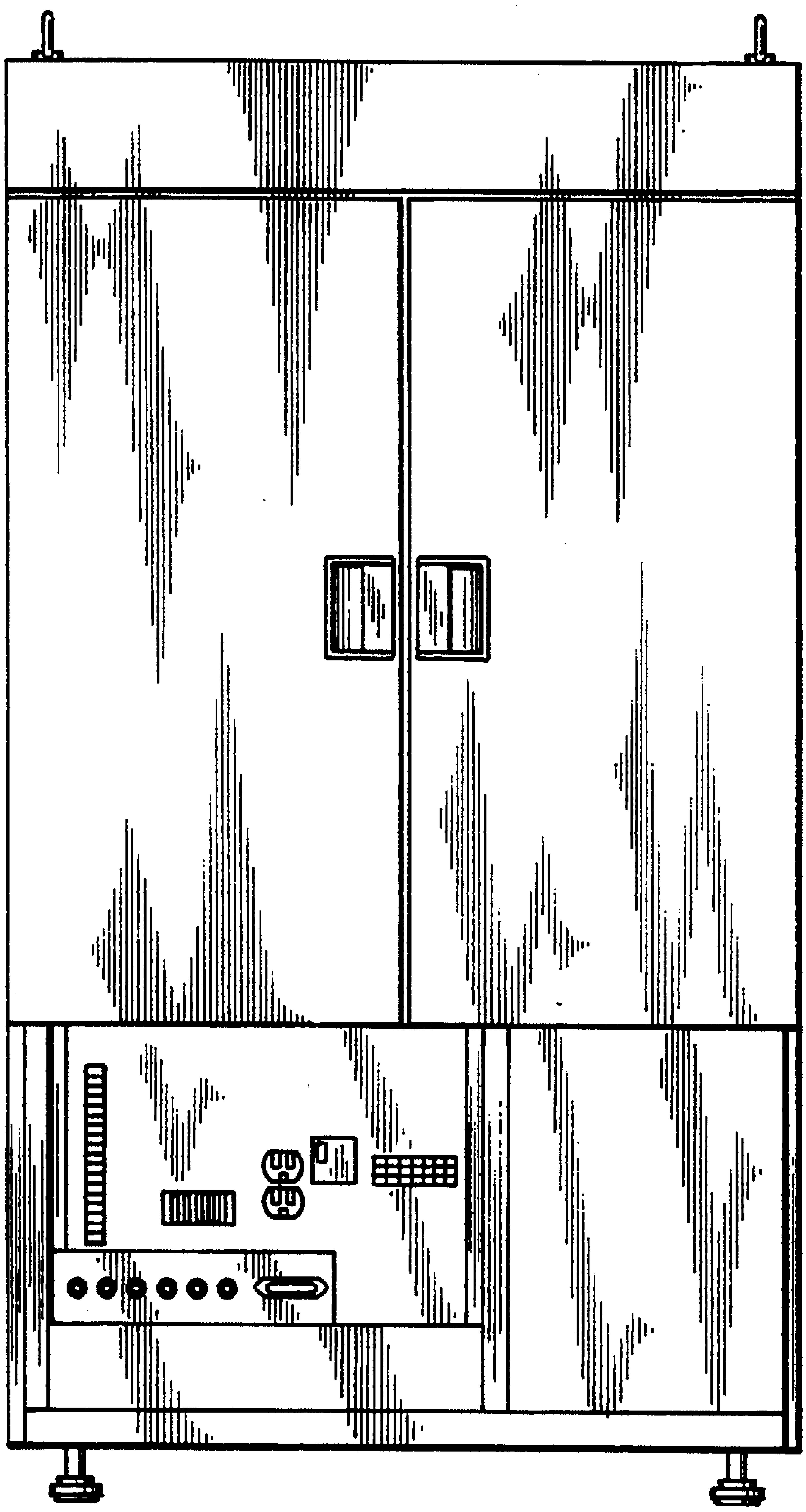

FIG. 8